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ABSTRACT

0045 A method for reducing light reflectance in photolithographic manufacturing process is disclosed including providing an inter-metal dielectric (IMD) layer including at least one via opening extending substantially perpendicular to a thickness therethrough, and, conformally forming an anti-reflectance coating (ARC) layer over (said) IMD layer such that the ARC layer is formed over sidewalls of the at least one via opening to reduce light reflectance.

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